

Title: METHOD FOR PROVIDING A LIFTOFF PROCESS
USING A SINGLE LAYER RESIST AND CHEMICAL
MECHANICAL POLISHING AND SENSOR FORMED THEREWITH
Applicants: Cyrille, et al.
Docket: HSJ920030027US1/HITG.025PA
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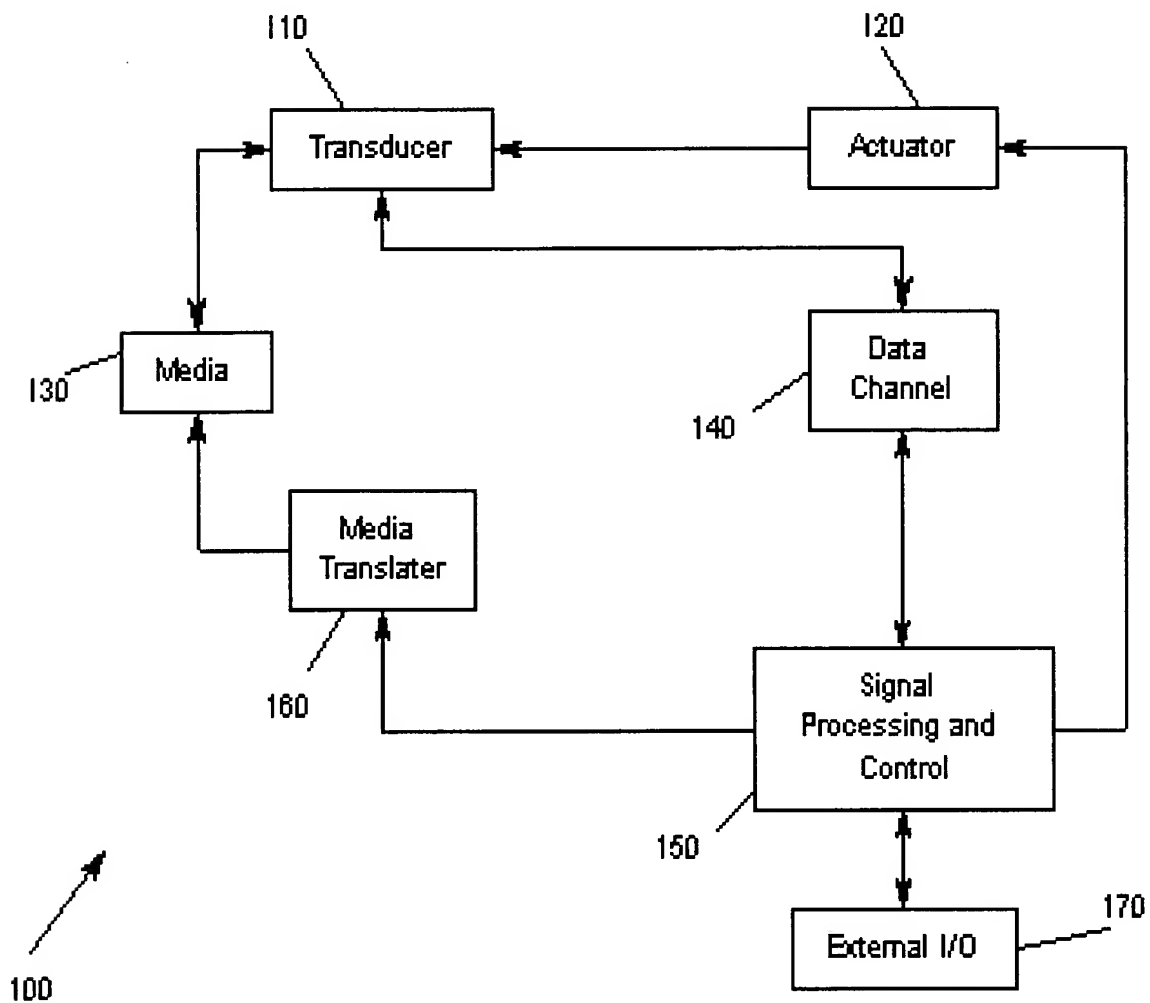


Fig. 1

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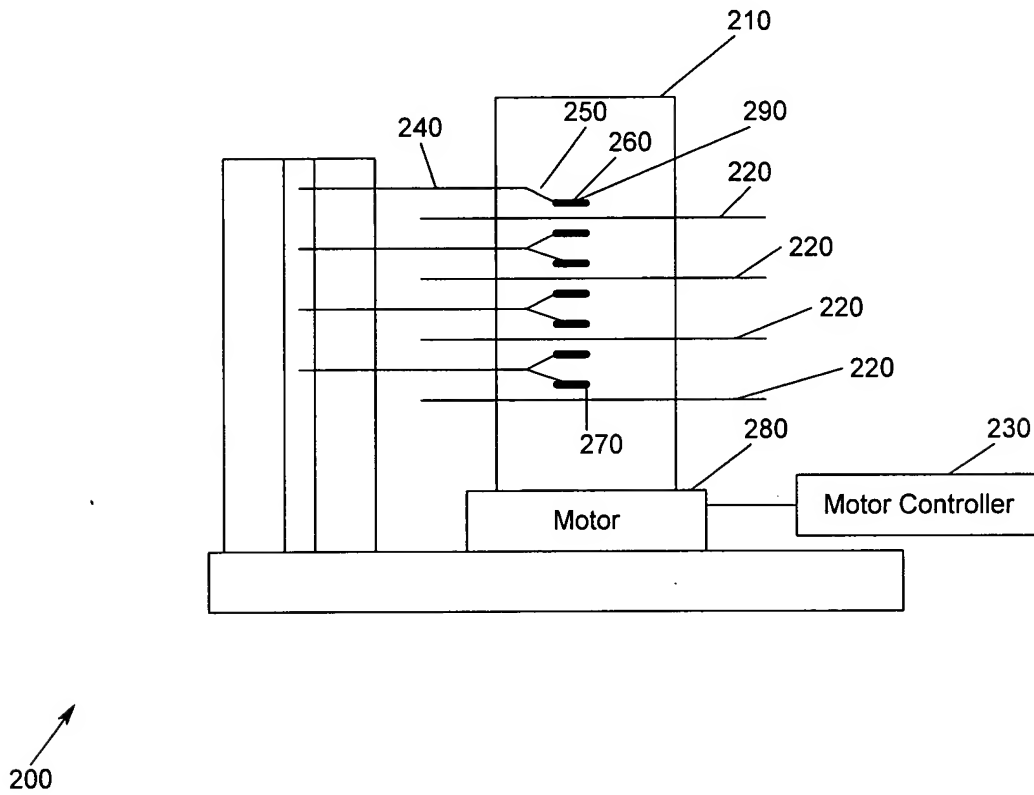


Fig. 2

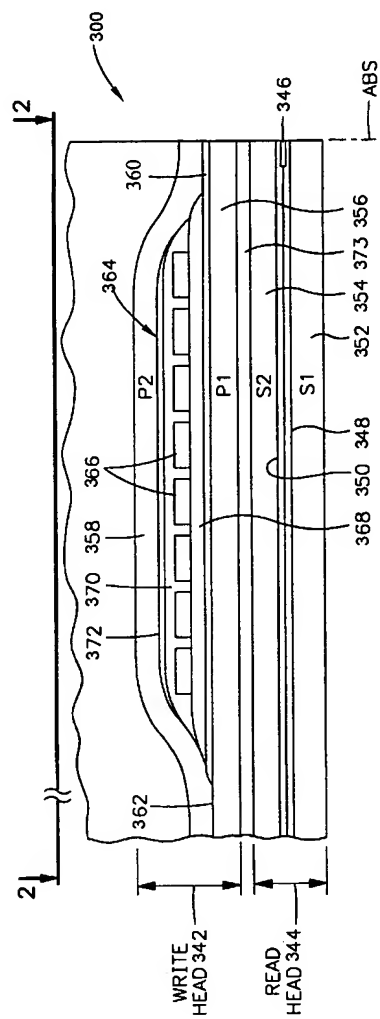


Fig. 3

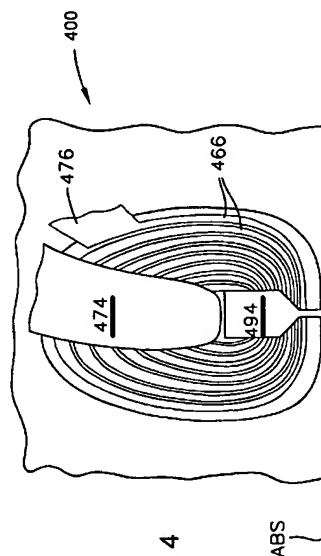


Fig. 4

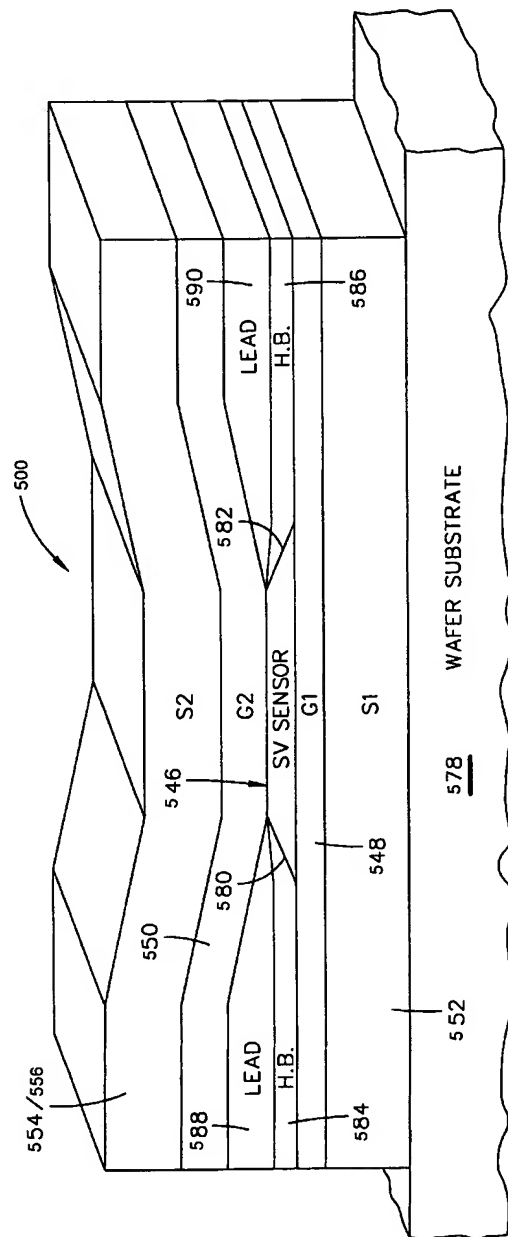


Fig. 5
 (ABS)

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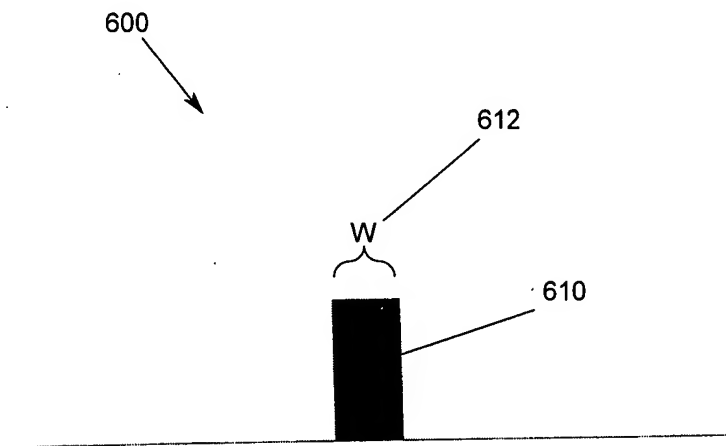


Fig. 6

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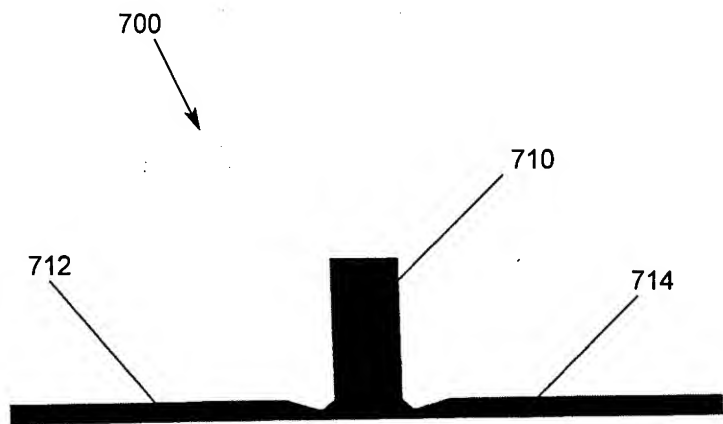


Fig. 7

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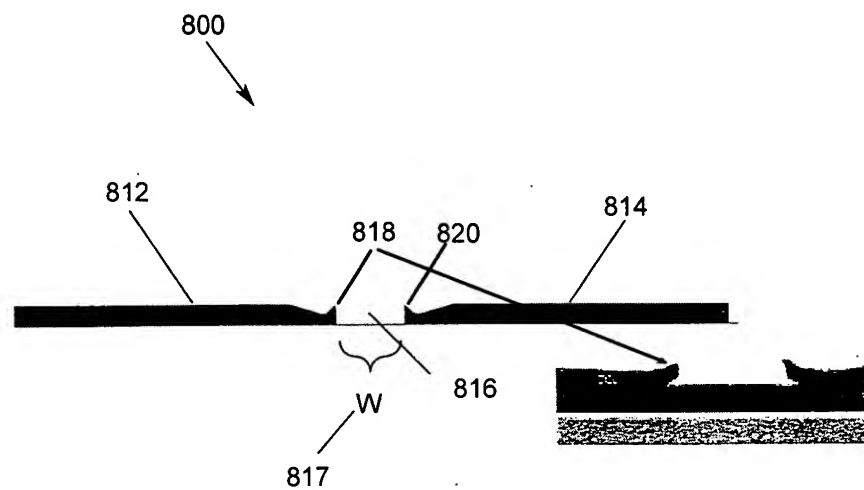


Fig. 8

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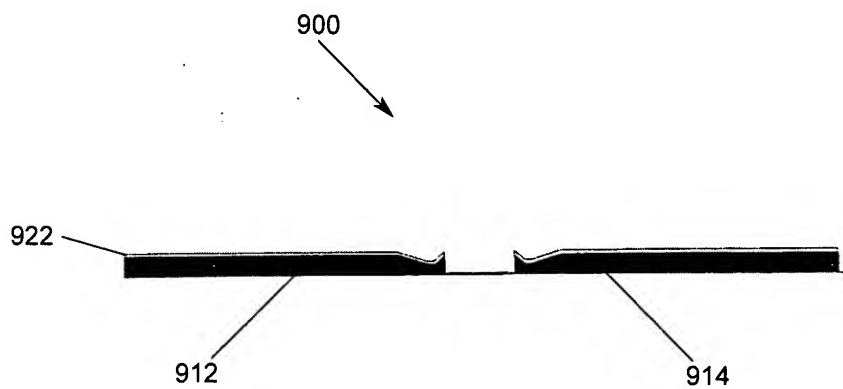


Fig. 9

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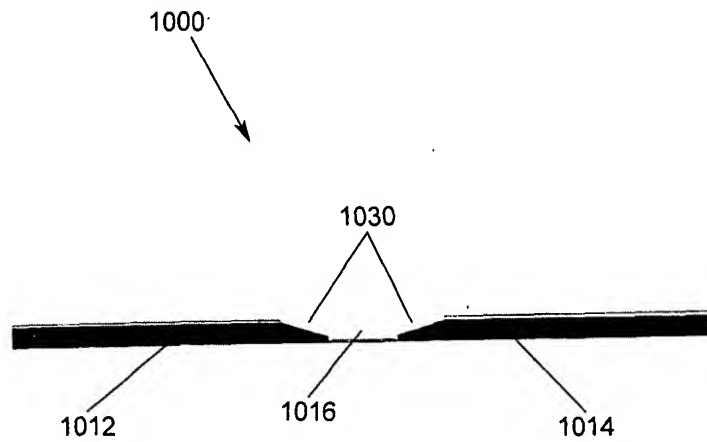


Fig. 10

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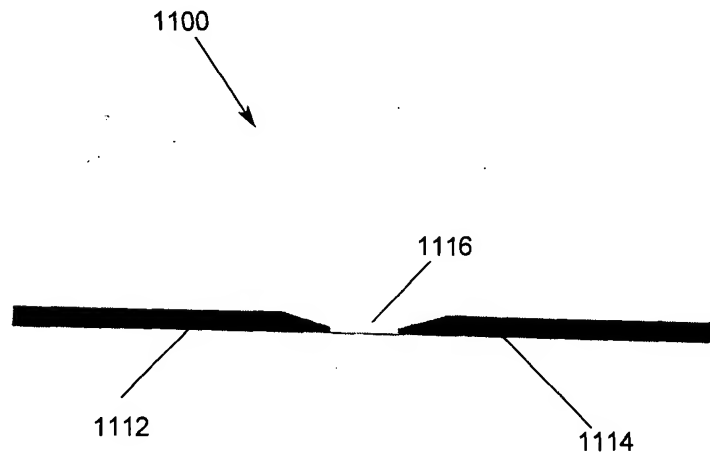


Fig. 11